

^{1st} Asia-Pacific Conference on Plasma Physics, 18-23, 09.2017, Chengdu, China Synthesis of diamond-like carbon thin films using helicon wave plasma CVD Peiyu Ji1,2, Jiawei Qian1,2,Chenggang Jin1,2,Lanjian Zhuge3 and Xuemei Wu1,2* 1College of Physics, Optoelectronics and Energy & Collaborative Innovation Center of Suzhou Nano Science and Technology, Soochow University, Suzhou 215006, China 2Key Lab of Advanced Optical Manufacturing Technologies of Jiangsu Province & Key Lab of Modern Optical Technologies of Education Ministry of China, Soochow University, Suzhou 215006, China 3Analysis and Testing Center, Soochow University, Suzhou 215123, China

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Properties of high-density Ar/CH4 plasmas with excitation of the m=1 mode helicon wave has been studied for reactive plasma synthesis of diamond like carbon (DLC) thin films. DLC was deposited on Si substrates by helicon wave plasma reactor. The reactive species of the helicon plasma in the reaction chamber were measured by the optical emission spectra (OES). OES show that the line emissions of CH and C2 were considerably enhanced in the helicon wave-excited high-density plasma. Plasma density and electron temperature was measured by Langmuir probe. The deposited DLC thin films were characterized by scanning electron microscopy (SEM) and Raman spectroscopy. It is found that an increase of the growth rate with the external magnetic field increase (from 1200G to 2400G). The I(D)/I(G) ratio and the G peak position decreased as a function of magnetic field, where the full width at half maximum (FWHM) of G peak increased. This indicates that the sp3 content increase.